

IN THE CLAIMS:

This listing of the claims replaces all prior versions and listings of the claims in this application.

The text of all pending claims (including any withdrawn claims) is set forth below. Canceled and not entered claims are indicated with claim number and status only. The claims as listed below show added text with underlining and deleted text with strikethrough. The status of each claim is indicated with one of (Original), (Currently amended), (Canceled), (Withdrawn), (Previously presented), (New), and (Not entered).

Please AMEND claims 14 and 18 and CANCEL claims 1-5, 7-13, 17, and 22 without prejudice or disclaimer in accordance with the following:

1.-13. (Canceled)

14. (Currently amended) A method of manufacturing an organic EL device, the method comprising:

forming a first electrode layer in a predetermined pattern on an insulating substrate;

forming an organic film comprising at least a patterned emission layer on the first electrode layer; and

forming a second electrode layer in a predetermined pattern on the organic film;

wherein the organic film and/or the second electrode layer are/is deposited using a deposition mask frame assembly, the deposition mask frame assembly comprising:

a flat mask comprising a flat thin plate in which a predetermined pattern of apertures is formed, the flat mask having a first flat surface extending over an entire area of the flat mask, and a second flat surface extending over the entire area of the flat mask, the second flat surface being separated from the first flat surface by a thickness of the mask;

a flat frame supporting the first flat surface of the flat mask so that the flat mask is tensed and the first flat surface remains flat; and

a flat cover mask supporting the second flat surface of the flat mask so that the second flat surface remains flat; and

wherein the flat mask, the flat frame, and the flat cover mask are held together by welds.

15. (Previously presented) The method of claim 14, wherein the flat mask is formed of nickel or an alloy of nickel and cobalt.

16. (Previously presented) The method of claim 14, wherein the flat mask is a flat electro-formed mask.

17. (Canceled)

18. (Currently amended) The method of claim ~~17~~ 14, wherein the welds are dot welds.

19. (Previously presented) The method of claim 18, wherein a welding pitch between the dot welds is 3 mm or less.

20. (Canceled)

21. (Previously presented) The method of claim 14, wherein the flat mask is tensed with different tensions at different points on each of a plurality of sides of the flat mask.

22. (Canceled)